

Fig. 4. Waveforms simulated for the *D*-band push-push VCO: (a) clipped signal at the two internal balanced outputs before the combiner and (b) waveform at double the frequency after the combiner.

was achieved by making the coplanar resonator between the two negative resistances continuous and by using an internal load resistance of $200\ \Omega$ instead of $50\ \Omega$. The biasing through a higher resistance together with the large voltage swing causes signal clipping at the two balanced outputs due to forward conduction of the base-collector diodes of Q5 and Q6. As shown in Fig. 4(a), due to this clipping, a strong even harmonic content can be generated.

The two differential signals are summed by a power combiner that is similar to a Wilkinson coupler. This coupler is designed to operate at the fundamental frequency, so the length of the line is a quarter-wavelength length at 70 GHz. While the output node of the combiner is seen as a short circuit for the differential mode of the oscillator core, the quarter-wavelength will transform this short circuit to an open circuit at the internal load resistor, making sure that the differential voltage swing at this point stays high enough to generate enough harmonic content. According to simulations, a voltage swing of about 160 mV at double the frequency is obtained after the combiner, as shown in Fig. 4(b).

A chip microphotograph of the oscillator is shown in Fig. 5. Again, the layout is done in a fully symmetric way using coplanar transmission lines. A good symmetry is crucial for a good suppression of the fundamental and odd harmonics at the output of the push-push VCO. The total chip size of the oscillator is 0.5 by 0.7 mm², including dc and RF probe pads.

III. DEVICE TECHNOLOGY AND PERFORMANCE

The *W*-band oscillators were realized using an all-optical lithography single-heterojunction InGaAs/InP HBT process, developed at Bell Laboratories, Lucent Technologies [7]. InGaAs/InP bipolar transistors offer the advantages over GaAs/AlGaAs HBTs of a lower turn-on voltage, higher electron mobility, better thermal dissipation, and better microwave performance, while still obtaining a high collector-to-base breakdown voltage. To improve device switching time and reduce power requirements, device dimensions have been continually decreased down to an emitter finger width of 1.2 μm . Obtaining these small device dimensions requires

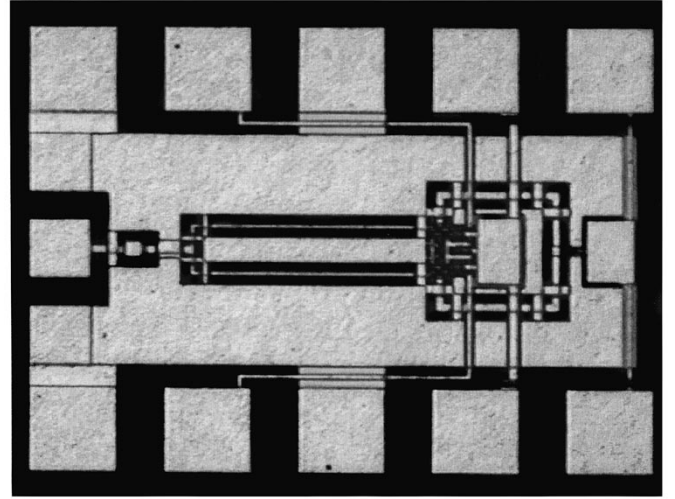


Fig. 5. Microphotograph of the *D*-band push-push VCO.

precise control of the fabrication process. We have developed a fabrication procedure for small and reliable InP-based HBTs using a process involving both wet etching and electron cyclotron resonance plasma etching, as described in more detail in [8]. HBTs with nominal 1.2 by 6 μm^2 emitter dimensions, measured on the same wafer as the oscillators, show a maximum cutoff frequency f_T of 150 GHz and a maximum oscillation frequency f_{max} in excess of 200 GHz. Fig. 6 shows the measured current gain and unilateral transducer power gain for a 1.2 by 6 μm^2 emitter device biased at a collector current of 5 mA, which is similar to the current of the devices in the *W*-band oscillator and slightly lower than the current for peak f_T . At this current, a transit frequency f_T of 135 GHz and a maximum oscillation frequency f_{max} of about 230 GHz can be extrapolated from measurements up to 110 GHz. The measured maximum available gain at 100 GHz is 6 dB, which should be sufficient for oscillator application at *W*-band.

The *D*-band push-push VCO was realized in an all-optical lithography single-heterojunction AlInAs/InGaAs HBT foundry process, developed and fabricated at HRL Laboratories, Malibu, CA [9]. HBTs with nominal 1 by 3 μm^2 emitter

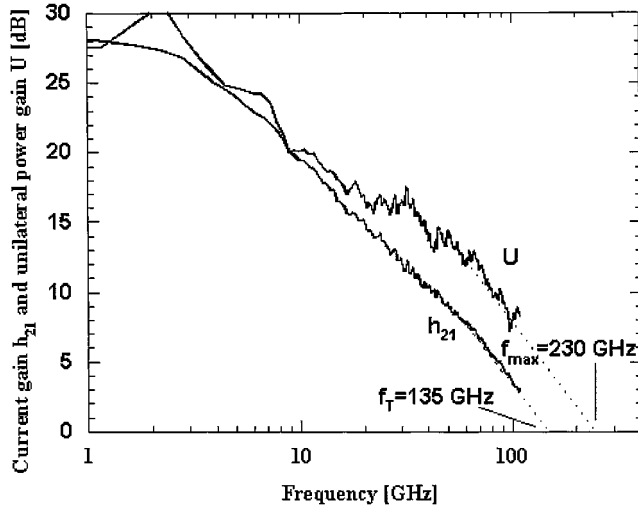


Fig. 6. Measured current gain and unilateral power gain and extrapolated f_T and f_{max} for a $1.2 \times 6 \mu\text{m}^2$ emitter single-heterojunction InGaAs/InP HBT biased at a collector current of 5 mA.

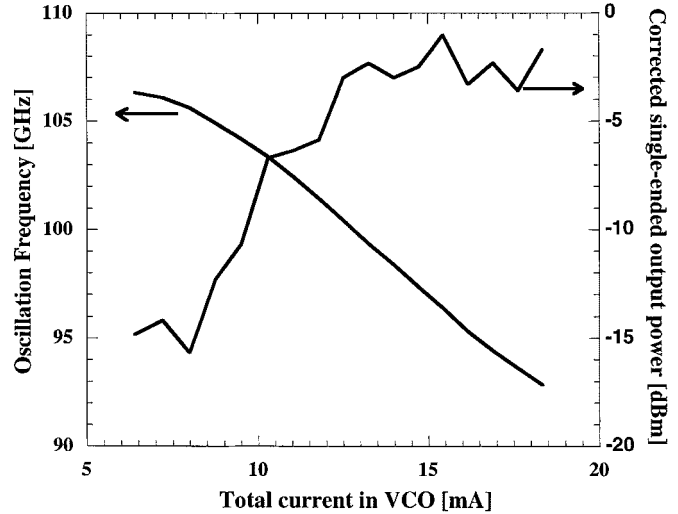


Fig. 8. Measured oscillation frequency and single-ended output power of the differential W-band oscillator as a function of the current in the VCO ($V_{EE} = -6$ V, $V_{tune} = -2.5$).

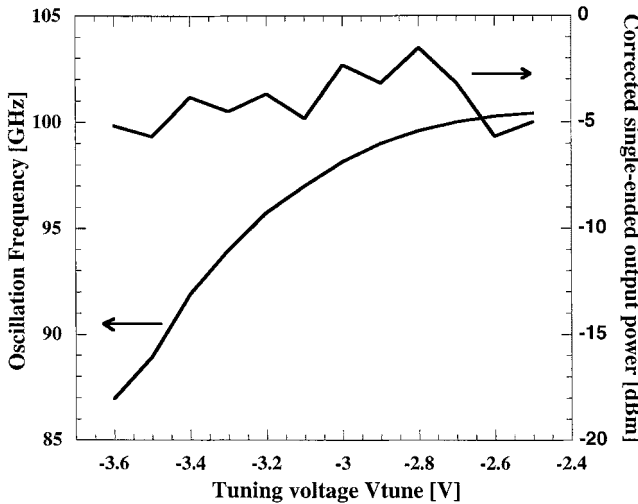


Fig. 7. Measured oscillation frequency and single-ended output power of the differential W-band oscillator as a function of the tuning voltage (total VCO current = 16 mA).

dimensions, measured on the same wafer as the oscillators, show a maximum cutoff frequency f_T of 150 GHz and a maximum oscillation frequency f_{max} of 170 GHz.

IV. RESULTS AND DISCUSSION

Spectral measurements from 75 to 110 GHz were performed using a 50-GHz spectrum analyzer extended in frequency with a Millitech CDA-10 75–100 GHz waveguide block downconverter. On-wafer measurements were performed using a dc to 110 GHz 1-mm coaxial probe connected to the WR-10 waveguide downconverter using a coaxial-to-waveguide transition.

The measured frequency of oscillation and output power versus the VCO tuning voltage is plotted in Fig. 7. A wide tuning range from 87 to 100 GHz is observed. The output power, which has been corrected for the mixer conversion loss and for loss in the probe and cables, is -3 dBm over the frequency range, constant to within our measurement error. For

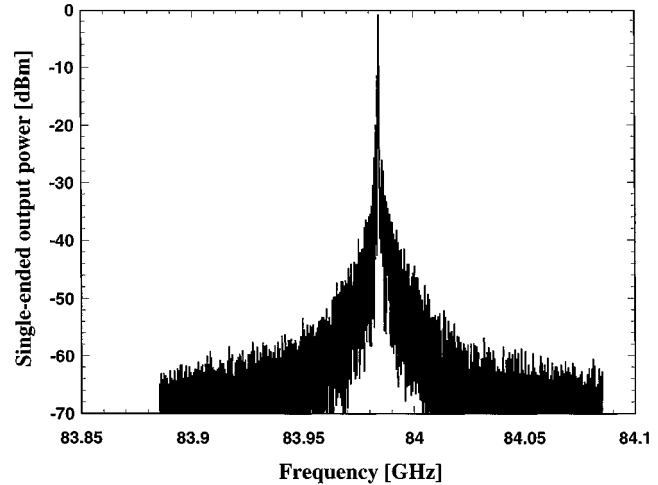


Fig. 9. Detail of the measured spectrum of the W-band VCO tuned for the lowest frequency.

the measurement, a bias voltage V_{EE} of -6 V and a total VCO current of 13 mA was applied. This bias current corresponds to an emitter current density of 80 kA/cm^2 and a total power dissipation of 78 mW.

By changing the current in the VCO, the tuning range can be further increased. As shown in Fig. 8, for a fixed tuning voltage of -2.5 V, the oscillation frequency can be decreased from 106 to 92 GHz by increasing the total current in the VCO from 6 to 18 mA. For the lowest currents, however, a decrease of the output power can be observed. By increasing the VCO current together with decreasing the voltage across the current mirror, a minimum oscillation frequency of 84 GHz can be obtained.

A detail of the measured spectrum of the VCO at this bias condition is shown in Fig. 9. The extremely high frequency and sensitivity to noise introduced by the bias supplies complicates an accurate determination of the phase noise. Depending on tuning frequency, a phase noise between -80 and -85 dBc/Hz at 1-MHz offset from the carrier can be estimated from the measured downconverted spectrum using a spectrum analyzer.

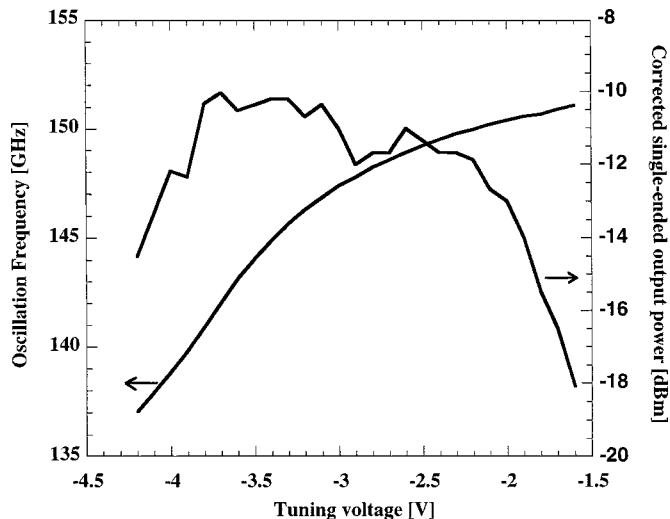


Fig. 10. Measured frequency tuning characteristics of the 150-GHz push-push VCO.

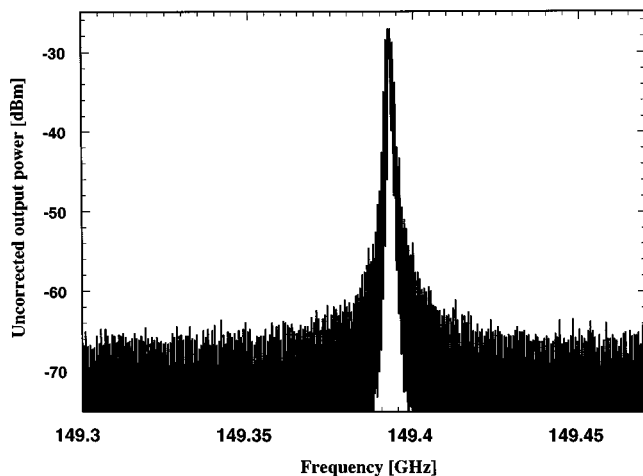


Fig. 11. Detail of the uncorrected measured spectrum of the 150-GHz push-push VCO (spectrum analyzer resolution and video bandwidth = 1 MHz; mixer losses are about 15 dB).

Mainly due to our extended tuning range, this value is about 5 dB higher than that of the lowest phase-noise monolithic *W*-band VCO (-88 dBc/Hz at 1-MHz offset [6]). The phase noise is better than those reported for HEMT VCOs with similar tuning range. For instance, a *W*-band HEMT oscillator with a phase noise of -67 dBc/Hz at 1 MHz was reported in [10].

Spectral measurements from 140 to 170 GHz on the *D*-band push-push VCO were performed on-wafer using a GGB Industries model 220 WR-05 waveguide probe together with a Millitech 140–170 GHz downconverter block, consisting of an active multiplier feeding a second-harmonic mixer. The measured frequency of oscillation versus tuning voltage is plotted in Fig. 10. An oscillation frequency between 137 and 151 GHz is obtained. The measured intermediate-frequency (IF) power from the downconverter is about -25 dBm. Taking a total down-conversion loss of the mixer, waveguide probe, and cables of about 15 dB, a maximum output power close to -10 dBm is obtained. Additional spectral measurements in *W*-band showed

that the fundamental frequency component of this second-harmonic oscillator is suppressed below the noise floor of the spectrum analyzer, indicating the good symmetry of a monolithic integration.

A detail of the measured spectrum of the push-push VCO is shown in Fig. 11. Again, the frequency and sensitivity to noise on the bias supplies complicates an accurate determination of the phase noise. From the downconverted IF spectrum, a phase noise of about -75 dBc/Hz at 1-MHz offset from the carrier is measured. This value is higher than that of the fundamental differential VCO due to the frequency doubling and also because the oscillator was designed for nonlinear operation.

V. CONCLUSIONS

Differential voltage-controlled oscillators operating up to 106 GHz were realized using InP HBT technology. By using the base-collector junction of the transistors in the current mirror as a varactor, a tuning range of 20% is achieved. This circuit is, to our knowledge, the first fully differential circuit operating in *W*-band. While using a compact differential topology with no reactive output matching or bias networks, the performance of this VCO in terms of phase noise, output power, and maximum frequency of operation is comparable with the best published monolithic *W*-band oscillators. This circuit will find application as the clock source in next-generation digital building blocks operating at speeds up to 100 Gb/s.

The differential topology is also used to extend the frequency range of integrated sources by using a push-push topology, as was demonstrated by the realization of a monolithic 136–150 GHz source. This VCO is the highest frequency integrated source based on bipolar technology, to the best of our knowledge. By using an InP-based HBT technology with higher maximum oscillation frequency, a further extension in the sub-millimeter-wave range could be obtained. Such oscillators will find application in ultra-high-speed lightwave and advanced imaging and remote sensing applications.

ACKNOWLEDGMENT

The authors would like to acknowledge the cooperation and excellent foundry management of M. Sokolich and L. Nguyen at HRL Laboratories, Malibu, CA. They thank M. Baker and P. Kinget for useful discussions.

REFERENCES

- [1] S. E. Rosenbaum, B. K. Kormanyos, L. M. Jelloian, M. Matloubian, A. S. Brown, L. E. Larson, L. D. Nguyen, M. A. Thompson, L. P. Katehi, and G. M. Rebeiz, "155- and 213-GHz AlInAs/GaInAs/InP HEMT MMIC oscillators," *IEEE Trans. Microwave Theory Tech.*, vol. 43, no. 4, pp. 927–932, 1995.
- [2] Y. Kwon, D. Pavlidis, T. L. Brock, and D. C. Streit, "A *D*-band monolithic fundamental oscillator using InP-based HEMT's," *IEEE Trans. Microwave Theory Tech.*, vol. 41, no. 12, pp. 2336–2344, 1993.
- [3] H. Wang, K. W. Chang, L. T. Tran, J. C. Cowles, T. R. Block, E. W. Lin, G. S. Dow, A. K. Oki, D. C. Streit, and B. R. Allen, "Low phase noise millimeter-wave frequency sources using InP-based HBT MMIC technology," *IEEE J. Solid-State Circuits*, vol. 31, no. 10, pp. 1419–1425, 1996.
- [4] K. Uchida, I. Aoki, H. Matsuura, T. Yakhara, S. Kobayashi, S. Oka, T. Fujita, and A. Miura, "104 and 134 GHz InGaP/InGaAs HBT oscillators," in *Proc. 1999 GaAs IC Symp.*, Monterey, CA, 1999, pp. 237–240.

- [5] J. R. Bender and C. Wong, "Push-push design extends bipolar frequency range," *Microwaves and RF*, pp. 91–98, Oct. 1983.
- [6] K. W. Kobayashi, A. K. Oki, L. T. Tran, J. Cowles, A. Gutierrez-Aitken, F. Yamada, T. Block, and D. C. Streit, "A 108-GHz InP-HBT monolithic push-push VCO with low phase noise and wide tuning bandwidth," *IEEE J. Solid-State Circuits*, vol. 34, no. 9, pp. 1225–1232, 1999.
- [7] R. F. Kopf, R. A. Hamm, R. W. Ryan, A. Tate, R. Pullela, G. Georgiou, J.-P. Mattia, and Y.-K. Chen, "Dry-Etch fabrication of reduced area InGaAs/InP HBTs," *J. Electron. Mater.*, vol. 29, no. 2, p. 222, 2000.
- [8] R. F. Kopf, R. A. Hamm, R. W. Ryan, J. Burm, A. Tate, Y.-K. Chen, G. Georgiou, D. V. Lang, and F. Ren, "Evaluation of encapsulation and passivation of InGaAs/InP DHBT devices for long-term reliability," *J. Electron. Mater.*, vol. 27, no. 8, pp. 954–964, 1998.
- [9] M. Sokolich, D. Docter, Y. Brown, A. Kramer, J. Jensen, W. Stanchina, S. Thomas, C. Fields, D. Ahmari, M. Lui, R. Martinez, and J. Duvall, "A low power 52.9 GHz static divider implemented in a manufacturable 180 GHz AlInAs/InGaAs HBT IC technology," in *Proc. IEEE GaAs IC Symp.*, Atlanta, GA, 1998, pp. 117–120.
- [10] A. Bangert, M. Schlechtweg, M. Lang, W. Haydl, W. Bronner, T. Fink, K. Kohler, and B. Raynor, "W-band MMIC VCO with a large tuning range using a pseudomorphic HFET," in *Proc. 1996 IEEE MTT-S Int. Microwave Symp.*, San Francisco, CA, 1996, pp. 525–528.

Yves Baeyens (S'89–M'96) received the M.S. and Ph.D. degrees in electrical engineering from the Catholic University of Leuven, Belgium, in 1991 and 1997, respectively.

His Ph.D. research was performed in cooperation with IMEC, Leuven, and treated the design and optimization of coplanar InP-based dual-gate HEMT amplifiers, operating up to W-band. After a one-and-a-half-year stay as a Visiting Scientist at the Fraunhofer Institute for Applied Physics, Freiburg, Germany, he is currently a Technical Manager in the High-Speed Electronics Research Department, Bell Laboratories, Lucent Technologies, Murray Hill, NJ. His research interests include the design of mixed analog–digital circuits for ultra-high-speed lightwave and millimeter-wave applications.

Claus Dorschky received the Dipl.Ing. degree from Friedrich Alexander Universität Erlangen, Germany, in 1986.

From 1986 to 1999, he was Member of Technical Staff in high-speed hardware development with the Optical Networking Group, Lucent Technologies, Nuremberg, Germany (former PKI), where he was responsible for high-speed integrated circuits, especially clock and data recovery. He has been involved in European research projects within the RACE and ACTS frameworks. Since 1999, he has been Technical Manager of the High Speed IC design group, responsible for full custom integrated circuits for optical interfaces above 10 Gb/s. He has contributed to about 15 publications and seven patents.

Nils Weimann (M'96) was born in Darmstadt, Germany, in August 1969. He received the M.S. degree in physics from Stuttgart University, Germany, in 1996 and the Ph.D. degree in electrical engineering from Cornell University, Ithaca, NY, in 1999.

His doctoral research involved electron transport in GaN and the design and fabrication of GaN microwave power transistors. In September 1999, he joined Bell Laboratories, Lucent Technologies, Murray Hill, NJ, as a Member of Technical Staff. His current research includes the technology, physics, and modeling of InP HBTs for high-speed analog and digital circuits.

Qinghung Lee was born in China. She received the Ph.D. degree in electrical engineering from University of California, Santa Barbara, in 1999.

In 1999, she joined the High Speed Electronics department of Bell Labs, Lucent Technologies. Her main interests are very high-frequency circuits for communication applications.

Rose Kopf received the B.S. degree in chemistry from Northeastern University, Boston, MA, in 1982 and the M.S. and Ph.D. degrees in materials science and engineering from Stevens Institute of Technology, Hoboken, NJ, in 1987 and 1991, respectively.

From 1978 to 1984, she was an Analytical Chemist with Arthur D. Little, Inc., Cambridge, MA. In 1984, she joined Bell Laboratories, Lucent Technologies, Murray Hill, NJ, where she was involved in MBE growth of GaAs/AlGaAs and InGaAs/InAlAs heterostructures for optical and electronic devices and circuits until 1992. Since then she has been involved in InP HBT process development for high-speed circuits. She has more than 200 publications in the semiconductor field and has received 16 patents.

George Georgiou was born in Greece in 1954. He received the Ph.D. degree in applied physics from Columbia University, New York, in 1980.

He joined Bell Laboratories, AT&T (now Lucent Technologies) in 1980 to develop submicrometer X-ray lithography systems. He has proceeded since then into process integration of novel gate and metal structures for submicrometer silicon CMOS. His current interest is mixed-signal IC design for high-speed lightwave communications systems using InP and SiGe HBT technologies.

John-Paul Mattia, photograph and biography not available at the time of publication.

Robert Hamm, photograph and biography not available at the time of publication.

Young-Kai Chen (S'78–M'86–SM'94–F'98) received the B.S.E.E. degree from National Chiao Tung University, Hsinchu, Taiwan, R.O.C., the M.S.E.E. degree from Syracuse University, Syracuse, NY, and the Ph.D. degree from Cornell University, Ithaca, NY, in 1988.

From 1980 to 1985, he was a Member of Technical Staff in the Electronics Laboratory of General Electric Company, Syracuse, responsible for the design of silicon and GaAs MMICs for phase array applications. Since 1988, he has been with Bell Laboratories, Murray Hill, NJ, as a Member of Technical Staff. Since 1994, he has been the Department Head of High Speed Electronics Research. He is also an Adjunct Associate Professor at Columbia University. His research interest is in high-speed semiconductor devices and circuits for wireless and fiber-optic communications. He has contributed to more than 90 technical papers and nine patents in the field of high-frequency electronics and semiconductor lasers.

Prof. Chen is a member of the American Physics Society and Optical Society of America.